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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE****Applicants:** Matthew J. Breitwisch, et al.**Docket:** BUR920040015US1 (17427)**Serial No.:** 10/710821**Dated:** June 7, 2004**Filed:** 08/05/04**For:** ISOLATED FULLY DEPLETED  
SILICON-ON-INSULATOR REGIONS BY  
SELECTIVE ETCHCommissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

Sir:

In accordance with 37 C.F.R. §§ 1.97 and 1.98, it is requested that the following reference, which is also listed on the attached Form PTO-1449, be made of record in the above-identified case.

1. M.Q. Huda, et al., "Technique for Large Elevation of Source/Drain Using Implantation Mediated Selective Etching", Electrochemical and Solid-State Letters, pp. G117-G118 (2003); and
2. Japanese Laid-Open Patent Application No. JP7007075A, filed on October 1, 1995, with English Language Translation.

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**CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents and Trademarks, P.O. Box 1450, Alexandria, VA 22313-1450 on

Dated:

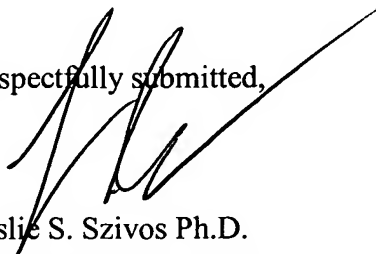
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*P. DelAngis*  
P. DelAngis

Applicants are submitting copies of the cited references, along with an English Abstract which explains the pertinence of the reference.

Inasmuch as this Information Disclosure Statement is being submitted in accordance with the schedule set out in 37 C.F.R. § 1.97(b), no petition, certification or fee is required.

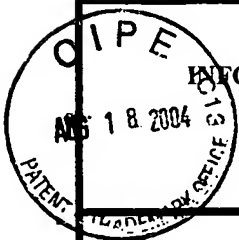
Respectfully submitted,



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**INFORMATION DISCLOSURE CITATION**  
(Use several sheets if necessary)

Docket Number (Optional)  
BUR920040015US1 (17427)

Application Number  
10/710821

Applicant(s)  
Matthew J. Breitwisch, et al.

Filing Date  
08/05/04

Group Art Unit  
Unassigned

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

**FOREIGN PATENT DOCUMENTS**

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
		JP7007075A	10/1/95	Japan				

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

		M.Q. Huda, et al., "Technique for Large Elevation of Source/Drain Using Implantation Mediated Selective Etching", <u>Electrochemical and Solid-State Letters</u> , pp. G117-G118 (2003).

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.